L	Hits	Search Text	DB	Time stamp
Number			<u> </u>	
1	350	polymeriz\$5 same acrylate same aqueous same acid same solvent	USPAT; US-PGPUB; EPO; JPO;	2002/12/04 10:09
2	5	(polymeriz\$5 same acrylate same aqueous same acid same solvent) and photoresist	DERWENT USPAT; US-PGPUB; EPO; JPO;	2002/12/04 10:09
3	31	polymeriz\$5 same acrylate same extract\$3 same aqueous same acid	DERWENT USPAT; US-PGPUB; EPO; JPO;	2002/12/04
6	18	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and photoresist	DERWENT USPAT; US-PGPUB; EPO; JPO;	2002/12/04 10:15
7	220	polymeriz\$5 same acrylate same wash\$3 same aqueous same acid	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:17
8	19	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:17
5	7	Synthesi\$4 same acrylate same wash\$3 same aqueous same acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:19
4	204	polymeriz\$5 same acrylate same wash\$3 same aqueous same acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 12:24
9	4	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and metal near remov\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 10:20
10	129596	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and maleic or fumaric or oxalic or malonic or adipic near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 12:26
11	115	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and (maleic or fumaric or oxalic or malonic or adipic near acid)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 12:49
12	7	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and oxalic near acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 12:51
13	0	(polymeriz\$5 same acrylate same wash\$3 same aqueous same acid) and aqueous near oxalic	USPAT; US-PGPUB; EPO; JPO;	2002/12/04 13:01
14	19	"4089806"	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 13:05
15	9	"4122000"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 13:43
16	88	metal near remov\$3 near chelat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 13:44
17	2	(metal near remov\$3 near chelat\$3) and oxalic	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/12/04 15:29

19 0 a356523   SPORTED   S	18		/#F072600#\ TV	T-2	00000/00/04
19	10	2	("5073622").PN.	USPAT;	2002/12/04
19				1	15:33
19				1	1
15:34   15:3		_		DERWENT	
20	19	0	a356523	USPAT;	1
DERWENT   JPO;   2002/12/04   15:34   2002/12/04   15:34   2002/12/04   15:34   2002/12/04   15:34   2002/12/04   15:34   2002/12/04				US-PGPUB;	15:34
200		ļ.		EPO; JPO;	
21				DERWENT	<u> </u>
21	20	0	a356523	JPO;	2002/12/04
22   13   "0356523"   DEWRINT JPO; 2002/12/04				DERWENT	15:34
15.34   15.34   15.34   15.37   15.3	21	0	a0356523		1
23   "0336523"   DERWENT   DERWENT   CO02/12/04		ļ		1	
2	22	13	"0356523"	<u> </u>	
2				1	1
196644   poly(meth) acrylate and metal near content   DERMENT US-PGPUB;   EPO; JPO; DERMENT US	23	2	"03056523"		1
- 496664 poly(meth)acrylate and metal near content content) and solvent near extraction content) and solvent near extraction content c		_		1	1
Content	_	496664	poly(meth)acrylate and metal near		1
- 496901 poly(meth)acrylate and metal near content				1	
A   A   A   A   A   A   A   A   A   A			Concent		14.14
- 496901 content content USPAT; 2002/12/02 14:05 EPO; JPO; DERWENT USPAT; 2002/12/02 14:06 EPO; JPO; DERWENT USPAT; 2002/12/02 14:00 EPO; JPO; DERWENT USPAT; 2002/12/02 14:02 EPO; JPO; DERWENT USPAT; 2002/12/02 14:02 EPO; JPO; DERWENT USPAT; 2002/12/02 14:03 EPO; JPO; DERWENT USPAT; 2002/12/02 USP-GPUB; EPO; JPO; DERWENT USPAT; 2002/12/02 USPAT				b and the second	
Content	1_	406001	malu/math\aamulata and matal mass		2002/12/02
### 4530 (poly(meth) acrylate and metal near content) and solvent near extraction	-	496901			,,
A530			Concent		14:05
2002/12/02   14:00   14:00   14:00   14:00   15:00   14:00					ļ
Content   and solvent near extraction   US-PGPUB;   14:00	1				
- 412 ((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3 (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid (((poly(meth)acrylate and metal near content) and acid near3 wash\$3) and polyprotic near acid (((poly(meth)acrylate and metal near content) USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid DERWENT (USPAT; uS-PGPUB; and acid near3 wash\$3) and polycathoxylic near acid uspat;	-	4530		· ·	
Content   Addition   Content		1	content) and solvent near extraction	US-PGPUB;	14:00
- 412 ((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3 - 0 (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid (((poly(meth)acrylate and metal near content) and acid near3 wash\$3) and polyprotic near acid (((poly(meth)acrylate and metal near content) and acid near3 wash\$3) and polycomboxylic near acid poly(meth)acrylate same metal near content USPAT; US-PGPUB; 14:03 - 496458 poly(meth)acrylate same reduced near metal near content USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DE				EPO; JPO;	1
Content   and solvent near extraction   and acid near3 wash\$3   DERWENT   Content				DERWENT	
and acid near3 wash\$3  (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid  (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid  (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polycarboxylic near acid polycarboxylic near acid  - 496458  - 496458  - 496443  - 496443  - 496449  - 496459  - 63722  and acid near3 wash\$3  And polyprotic near acid (((poly(meth)acrylate same metal near content) poly(meth)acrylate same reduced near metal near content  - 504390  - 63722  and acid near3 wash\$3  And polyprotic near acid ((poly(meth)acrylate same reduced near metal near content) poly(meth)acrylate same reduced same metal near content) poly(meth)acrylate same reduced same metal near content) poly(meth)acrylate same reduced same metal near content) same solvent same near near near near near near near nea	-	412	((poly(meth)acrylate and metal near	USPAT;	2002/12/02
and acid near3 wash\$3  (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid  (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid  (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polycarboxylic near acid polycarboxylic near acid  - 496458  - 496458  - 496443  - 496443  - 496449  - 496459  - 63722  and acid near3 wash\$3  And polyprotic near acid (((poly(meth)acrylate same metal near content) poly(meth)acrylate same reduced near metal near content  - 504390  - 63722  and acid near3 wash\$3  And polyprotic near acid ((poly(meth)acrylate same reduced near metal near content) poly(meth)acrylate same reduced same metal near content) poly(meth)acrylate same reduced same metal near content) poly(meth)acrylate same reduced same metal near content) same solvent same near near near near near near near nea			content) and solvent near extraction)	US-PGPUB;	14:02
Content   Cont				EPO; JPO;	
- 0 (((poly(meth) acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polyprotic near acid (((poly(meth) acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polycarboxylic near acid polycarboxylic near acid polycarboxylic near acid poly(meth) acrylate same metal near content USPAT; US			,	1	
Content   and solvent near extraction   and acid near3 wash\$3   and polyprotic near acid   ((poly(meth)acrylate and metal near content)   and acid near3 wash\$3)   and polyprotic near acid   ((poly(meth)acrylate and metal near content)   and acid near3 wash\$3)   and polycarboxylic near acid   DERWENT   USPAT;   2002/12/02   14:03    -	_	l 0	(((poly(meth)acrylate and metal near		2002/12/02
and acid near3 wash\$3) and polyprotic near acid (((poly(meth)acrylate and metal near content) and solvent near extraction) and acid near3 wash\$3) and polygrotic near acid uspat;					
near acid   (((poly(meth) acrylate and metal near content) and solvent near extraction)   and acid near3 wash\$3) and polycarboxylic near acid   poly(meth) acrylate same metal near content   USPAT;   USPGPUB;   EPO; JPO;   DERWENT   USPAT;   USP				1	11100
Content   Age   Content   Ag					
Content   and solvent near extraction   and acid near   wash\$3   and   polycarboxylic near acid   polycarboxylic near acid   polycarboxylic near acid   poly(meth) acrylate   same   metal   near   uspat;   content   uspat	l <u>-</u>	28			2002/12/02
and acid near3 wash\$3) and poly(meth) acrylate same metal near content USPAT; 2002/12/02 14:06  496458 poly(meth) acrylate same reduced near metal near content USPAT; 2002/12/02 14:06  496443 poly(meth) acrylate same reduced near metal near content USPAT; 2002/12/02 14:13  - 496459 poly(meth) acrylate same reduced same metal same content USPAT; 2002/12/02 14:08  - 504390 poly(meth) acrylate same metal USPAT; 2002/12/02 14:08  - 853 (poly(meth) acrylate same metal USPAT; 2002/12/02 14:09  - 63722 solvent same extraction USPAT; 2002/12/02 14:14  - 4 ((poly(meth) acrylate same reduced same metal same content) same solvent same metal uspat; 2002/12/02 14:14  - (poly(meth) acrylate same reduced same metal uspat; 2002/12/02 14:14  - (poly(meth) acrylate same reduced same metal uspat; 2002/12/02 14:14  - (poly(meth) acrylate same reduced same metal uspat; 2002/12/02 14:14  - (poly(meth) acrylate same reduced same metal same content) same solvent same uspat; 2002/12/02 14:14  - (poly(meth) acrylate same reduced same metal same content) same solvent same uspat; 2002/12/02 14:14  - (poly(meth) acrylate same reduced same metal uspat; 2002/12/02 14:14  - (poly(meth) acrylate same reduced same metal uspat; 2002/12/02 14:19  - (poly(meth) acrylate same reduced same metal uspat; 2002/12/02 14:19			, , , , , , , , , , , , , , , , , , ,		1 ' '
polycarboxylic near acid poly(meth) acrylate same metal near uspan; content uspan; lat:06  496443 poly(meth) acrylate same reduced near metal near content uspan; lat:06  496459 poly(meth) acrylate same reduced same uspan; lat:08  - 496459 poly(meth) acrylate same reduced same metal uspan; lat:08  - 504390 poly(meth) acrylate same metal uspan; lat:08  - 504390 poly(meth) acrylate same metal uspan; lat:09  - 853 (poly(meth) acrylate same reduced same metal same content) same solvent same extraction uspan; lat:14  - 63722 solvent same extraction uspan; lat:14  - ((poly(meth) acrylate same reduced same metal same content) same solvent same extraction uspan; lat:14  - ((poly(meth) acrylate same reduced same metal same content) same solvent same extraction uspan; lat:14  - ((poly(meth) acrylate same reduced same metal same content) same solvent same extraction uspan; lat:14  - ((poly(meth) acrylate same reduced same metal same content) same solvent same uspan; lat:14  - ((poly(meth) acrylate same reduced same metal same content) same solvent same uspan; lat:14  - ((poly(meth) acrylate same reduced same metal same content) same solvent same uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:14  - ((poly(meth) acrylate same reduced same metal uspan; lat:1		j		1	14.05
- 496458 poly(meth)acrylate same metal near content				1	
Content	l <u>-</u>	496458		1	2002/12/02
496443 poly(meth)acrylate same reduced near metal near content uspat; us-pGpUB; EPO; JPO; DERWENT uspat; us-pGpUB; EPO; JPO; DERWENT uspat; netal same content uspat; us-pGpUB; EPO; JPO; DERWENT uspat; netal same content uspat; netal same content uspat; netal uspat; netal same extraction uspat; netal same content) same solvent same netal uspat; netal same content) same reduced same netal uspat; netal same content uspat; netal same uspat; netal same content uspat; netal same content uspat; netal same content uspat; netal same uspa		130130			
- 496443 poly(meth)acrylate same reduced near metal near content USPAT;			Content	1	14.00
- 496443 poly(meth)acrylate same reduced near metal near content USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO;					
Metal near content		1000440	males/math\		2002/20/20
- 496459 poly(meth)acrylate same reduced same metal uspat; us-pgpuB; poly(meth)acrylate same metal uspat; us-pgpuB; poly(meth)acrylate same metal uspat; us-pgpuB; poly(meth)acrylate same reduced same metal uspat; us-pgpuB; pepo; Jpo; perwent uspat; us-pgpuB; pepo; Jpo; perwent uspat; uspa	-	496443	1 2 - 2 ,	1	
- 496459 poly(meth)acrylate same reduced same metal uspat; us-pgpuB; EPO; JPO; DERWENT uspat; 2002/12/02 uspat; 2002/12/			metal near content	,	14:13
- 496459 poly(meth)acrylate same reduced same metal same content USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; US-P				1	[
metal same content    US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EXTRACTION) same aqueous near acid EPO; JPO;	1			1	<u> </u>
- 504390 poly(meth)acrylate same metal USPAT; 2002/12/02 US-PGPUB; EPO; JPO; DERWENT USPAT; U	1 -	496459			
- 504390 poly(meth)acrylate same metal USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; Metal same content) same solvent same extraction USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; Metal same content) same reduced same metal uspat; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EXTRACTION) same aqueous near acid EPO; JPO;	1		metal same content	US-PGPUB;	14:08
- 504390 poly(meth)acrylate same metal USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; 2002/12/02 14:09  - 853 (poly(meth)acrylate same reduced same metal uspat; 2002/12/02 14:14  - 63722 solvent same extraction USPAT; 2002/12/02 14:14  - 4 ((poly(meth)acrylate same reduced same metal uspat; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US				EPO; JPO;	
US-PGPUB; EPO; JPO; DERWENT USPAT; 2002/12/02 metal same content) same solvent same EPO; JPO; DERWENT USPAT; 2002/12/02 l4:14  - 63722 solvent same extraction USPAT; 2002/12/02 US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; EPO; JPO; DERWENT USPAT; USP				DERWENT	
US-PGPUB; EPO; JPO; DERWENT USPAT; 2002/12/02 metal same content) same solvent same EPO; JPO; DERWENT USPAT; 2002/12/02 l4:14  - 63722 solvent same extraction USPAT; 2002/12/02 US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; EPO; JPO; DERWENT USPAT; USP	-	504390	poly(meth)acrylate same metal	USPAT;	2002/12/02
- 853 (poly(meth)acrylate same reduced same metal same content) same solvent same (USPAT; 2002/12/02 14:14 EPO; JPO; DERWENT USPAT; US-PGPUB; EVERT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USPGPUB; EXTRACTION) same aqueous near acid EPO; JPO;	1		·	US-PGPUB;	14:09
- 853 (poly(meth)acrylate same reduced same metal same content) same solvent same (USPAT; USPAT; US-PGPUB; Extraction (Poly(meth)acrylate same reduced same (USPAT; US-PGPUB; EPO; JPO; DERWENT (USPAT; US-PGPUB; EPO; JPO; DERWENT (USPAT; US-PGPUB; EPO; JPO; DERWENT (USPAT; USPAT; USP				1	
- 853 (poly(meth)acrylate same reduced same metal same content) same solvent same (USPAT; US-PGPUB; 14:14 EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USPA	1				]
metal same content) same solvent same  extraction  G3722 solvent same extraction  G3723 solvent same extraction  G3724 solvent same extraction  G3724 solvent same extraction  G3725 solvent same extraction  G3726 solvent same extraction  G3727 solve	-	853	(poly(meth)acrylate same reduced same	1	2002/12/02
extraction  63722 solvent same extraction  50722 solvent same extraction  63722 solvent same extraction  63723 solvent same extraction  63724 solvent same extraction  63724 solvent same extraction  63725 solvent same extraction  63725 solvent same extraction  63726 solvent same extraction  63727 solvent same extraction  63726 solvent same			, ,, , , , , , , , , , , , , , , , , , ,		
- 63722 solvent same extraction USPAT; 2002/12/02 US-PGPUB; EPO; JPO; DERWENT  4 ((poly(meth)acrylate same reduced same metal same content) same solvent same uspat; USPAT; 2002/12/02 US-PGPUB; extraction) same aqueous near acid EPO; JPO;			1	1	
- 63722 solvent same extraction USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USPAT				1	1
US-PGPUB; 14:14  EPO; JPO; DERWENT  ((poly(meth)acrylate same reduced same uSPAT; 2002/12/02 metal same content) same solvent same uS-PGPUB; extraction) same aqueous near acid EPO; JPO;	-	63722	solvent same extraction	l .	2002/12/02
EPO; JPO; DERWENT  ((poly(meth)acrylate same reduced same uspar; 2002/12/02 metal same content) same solvent same uspar; 2002/12/02 table to the same extraction) same aqueous near acid EPO; JPO;		03,22	Solvene Same enclared	i .	
The determinant of the content of th					1
- 4 ((poly(meth)acrylate same reduced same USPAT; 2002/12/02 metal same content) same solvent same USPAT; US-PGPUB; 14:19 extraction) same aqueous near acid EPO; JPO;				i e	
metal same content) same solvent same US-PGPUB; 14:19 extraction) same aqueous near acid EPO; JPO;	l _		((noly/meth)acrylate same reduced same	i .	2002/12/02
extraction) same aqueous near acid EPO; JPO;	_	4		1	1
	1	1		1	14:13
DERWENT			extraction) same aqueous near acid		
	L	L		DERWENT	

-	496858	poly(meth)acrylate same photoresist	USPAT;	2002/12/02
			US-PGPUB;	16:17
			EPO; JPO;	
			DERWENT	j
-	3	polyacrylate same photoresist and metal	USPAT;	2002/12/02
		near content	US-PGPUB;	14:21
			EPO; JPO;	1
			DERWENT	
_	159	polyacrylate same photoresist	USPAT;	2002/12/02
			US-PGPUB;	16:06
			EPO; JPO;	
			DERWENT	(
_	887236	poly(meth)acrylate same photoresistsame	USPAT;	2002/12/02
		purif\$8	US-PGPUB;	16:17
		P412140	EPO; JPO;	10.1,
			DERWENT	
_	496445	poly(meth)acrylate same photoresist	USPAT;	2002/12/02
		same purif\$8	US-PGPUB;	16:26
		Same partito	EPO; JPO;	10.20
1			DERWENT	
_	497666	poly(meth)acrylate same purif\$8	USPAT;	2002/12/02
	497000	pory/meth/acryrace same purition	•	2002/12/02
	1		US-PGPUB;	16:18
	1		EPO; JPO;	
}	1367	(males/math) = musl = h = 1	DERWENT	1 2002 (22 (22
! -	1367	(poly(meth)acrylate same photoresist	USPAT;	2002/12/02
	1	same purif\$8) same metal same content	US-PGPUB;	16:19
İ			EPO; JPO;	
			DERWENT	
-	40	((poly(meth)acrylate same photoresist	USPAT;	2002/12/02
		same purif\$8) same metal same content)	US-PGPUB;	16:20
ĺ		and wash\$3 near3 acid	EPO; JPO;	
			DERWENT	
+	245857	purif\$8 same process same	USPAT;	2002/12/02
		poly(meth)acrylate	US-PGPUB;	16:28
			EPO; JPO;	
]			DERWENT	
-	17	(purif\$8 same process same	USPAT;	2002/12/02
,	-	poly(meth)acrylate) and reduced near	US-PGPUB;	16:31
		metal near content	EPO; JPO;	1 20.01
			DERWENT	
<del>-</del>	8	ochiai near koshiro.in.	USPAT;	2002/12/02
			US-PGPUB;	16:49
			EPO; JPO;	10.15
			DERWENT	
_	3	"6258507"	USPAT;	2002/12/02
		0230307	US-PGPUB;	
				10.50
			EPO; JPO; DERWENT	
_	252194	purif\$8 same poly(meth)acrylate		2002/12/02
	232134	Partito same bory (mech) activate	USPAT;	2002/12/02
			US-PGPUB;	16:51
			EPO; JPO;	
	1256	/mini 600 nama walkataka 2 1 1	DERWENT	2002/22/22
_	1256	(purif\$8 same poly(meth)acrylate) same	USPAT;	2002/12/02
		photoresist	US-PGPUB;	17:06
			EPO; JPO;	
			DERWENT	
-	4		USPAT;	2002/12/02
		photoresist) same metal same content	US-PGPUB;	16:53
			EPO; JPO;	
			DERWENT	
-	36	((purif\$8 same poly(meth)acrylate) same	USPAT;	2002/12/02
		photoresist) and metal same content	US-PGPUB;	16:53
		-	EPO; JPO;	
			DERWENT	
_	8	((purif\$8 same poly(meth)acrylate) same	USPAT;	2002/12/02
		photoresist) same metal near ions	US-PGPUB;	17:09
		Land House Tours	EPO; JPO;	
			DERWENT	
L	L	<u> </u>	~~~ × × × × × × × × × × × × × × × × × ×	

-	820	metal near ions near removal	USPAT;	2002/12/03
			US-PGPUB;	17:13
			EPO; JPO;	
_	80	(purif\$8 same poly(meth)acrylate) and	DERWENT	2002/12/02
		(metal near ions near removal)	USPAT; US-PGPUB;	2002/12/02 17:16
		( sar near rous near removar)	EPO; JPO;	17:10
			DERWENT	
-	12	(metal near ions near removal) same	USPAT;	2002/12/02
		aqueous near acid	US-PGPUB;	17:26
		_	EPO; JPO;	
			DERWENT	
-	1	( the sale from following from the first from the f	USPAT;	2002/12/02
		wash\$3 near aqueous near acid	US-PGPUB;	17:27
			EPO; JPO;	j
			DERWENT	1
-	235455	purif\$7 near poly(meth)acrylate	USPAT;	2002/12/03
	1		US-PGPUB;	09:52
			EPO; JPO;	
			DERWENT	
-	24269	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	USPAT;	2002/12/03
	1	near extraction	US-PGPUB;	09:54
			EPO; JPO;	
			DERWENT	
1 -	41	wash near aqueous near acid	USPAT;	2002/12/03
İ	i		US-PGPUB;	09:54
	-		EPO; JPO;	
_	2131	(murif67 man malu(math) as mulata)	DERWENT	2002/12/22
	2131	(purif\$7 near poly(meth)acrylate) and (wash near aqueous near acid or solvent	USPAT;	2002/12/03
		near extraction)	US-PGPUB;	09:54
		TOOL CACINCULOILY	EPO; JPO; DERWENT	
_	276	aqueous near acid near extraction	USPAT;	2002/12/03
	]	Hour dord Hour extraction	US-PGPUB;	09:54
			EPO; JPO;	09.34
			DERWENT	
-	9485	aqueous near acid and extraction	USPAT;	2002/12/03
		1 and onordoron	US-PGPUB;	09:55
			EPO; JPO;	""."
			DERWENT	
-	36	(purif\$7 near poly(meth)acrylate) and	USPAT;	2002/12/03
		(aqueous near acid near extraction)	US-PGPUB;	09:56
		,	EPO; JPO;	
			DERWENT	
-	0	polyacrylate and purif7	USPAT;	2002/12/03
			US-PGPUB;	09:56
			EPO; JPO;	
			DERWENT	
-	4409	polyacrylate and purif\$7	USPAT;	2002/12/03
			US-PGPUB;	10:08
			EPO; JPO;	
_	7450	maluaguulaha aya aaaa 547	DERWENT	0000 405 455
j <sup>-</sup>	7450	polyacrylate and purif\$7	USPAT;	2002/12/03
			US-PGPUB;	09:57
			EPO; JPO;	
_	248	(nolyacrylate and munifer)	DERWENT	2002/12/02
	240	<pre>(polyacrylate and purif\$7) and photoresist</pre>	USPAT;	2002/12/03
		buccoreatac	US-PGPUB;	09:57
			EPO; JPO;	
_	4	polyacrylate and trace near metal near	DERWENT	2002/12/02
	3	ion near remov\$3	USPAT;	2002/12/03
		Tou Heat Temovol	US-PGPUB;	10:09
			EPO; JPO;	
_	40	(polyacrylate and metal near ion near	DERWENT USPAT;	2002/12/03
	30	remov\$3) and wash	US-PGPUB;	10:11
		TTIMETTO / MIM HADII	EPO; JPO;	10.11
			DERWENT	
·	· · · · · · · · · · · · · · · · · · ·		221/4/11/17	

169038					
169038	-	120	polyacrylate and metal near ion near	1 '	
169038			Temov\$3		10:11
169038   polymerization and poly(meth)acrylate and extraction   (polymerization and poly(meth)acrylate and extraction) and aqueous near oxalic   (polymerization and poly(meth)acrylate and extraction) and metal near remov\$3   (polymerization and poly(meth)acrylate and extraction) and metal near remov\$3   (polymerization and poly(meth)acrylate and extraction) and metal near remov\$3   (polymerization and poly(meth)acrylate and extraction) and metal near remov\$3   us-PeguB; polymopoly   (polymerization and poly(meth)acrylate and extraction) and metal near remov\$3   us-PeguB; polymopoly   (polymerization and poly(meth)acrylate and extraction) and aqueous near oxalic   us-PeguB; polymopoly(meth)acrylate and extraction) and aqueous near oxalid   us-PeguB; polymopoly(meth)acrylate and extraction) and aqueous near acid and extraction) and aqueous near acid and extraction) and aqueous near acid and extraction) and aqueous near acid and extraction) and aqueous near acid and extraction) and poly(meth)acrylate and extraction) and polymeth)acrylate and extraction) and polymeth)acrylate used extraction) and metal near remov\$3   us-PeguB; polymopoly(meth)acrylate and extraction) and polymopolymeth)acrylate and extraction) and polymeth)acrylate used extraction) and aqueous near acid used extraction) and polymeth)acrylate used extraction   used extraction) and polymopolymeth)acrylate used extraction   used extraction)   used extraction   used extraction)   used extraction)   used extraction)   used extraction)   used extraction)   used extraction)   used extrac	İ			1	
100   (polymerization and poly(meth)acrylate and extraction) and aqueous near oxalic near acid   (polymerization and poly(meth)acrylate and extraction) and metal near remov\$3   US-PGPUB, EPO, JPO, DERWENT   USPAT;   U	-	169038	polymerization and poly(meth)acrylate		2002/12/03
100					
100				EPO; JPO;	
and extraction   and aqueous near oxalic   near acid	1_	100	/malemoniantian and male ( 11)		
Near acid	-	100		1	
102				1	14:16
102					
and extraction   and metal near remov\$3   US-PGPUB;   15:04   EPO; JPO; JPO; JPO; JPO; JPO; JPO; JPO; J	-	845	(polymerization and poly(meth)acrylate		2002/12/03
102   ((polymerization and poly(meth)acrylate and extraction) and metal near remov\$3)   USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; USP			and extraction) and metal near remov\$3		1
102					
and extraction) and metal near remov\$3   US-PGPUB; ED: JPO; DERWENT USPAT; USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PGPUB; EPO; JPO; DEWENT USPAT; US-PGPUB; EPO; JPO; DERWENT USPAT; US-PG	_	102	//polymorization and noly/math)	3	0000 100 100
and photoresist  ((polymerization and poly(meth)acrylate and extraction)) and metal near remov\$3) and aqueous near oxalic  (polymerization and poly(meth)acrylate and extraction) and aqueous near oxalic  (polymerization and poly(meth)acrylate and extraction) and aqueous near acid (polymerization and poly(meth)acrylate and extraction) and aqueous near acid (polymerization and poly(meth)acrylate and extraction) and aqueous near acid (polymerization and poly(meth)acrylate and extraction) and aqueous near acid (polymerization and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate with reduc\$4 with metal with content (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solewnt near extraction  ((polymeth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solewnt near extraction  ((polymeth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solewnt near extraction  ((polymeth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solewnt near extraction  ((polymeth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solewnt near extraction  ((polymeth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solewnt near extraction  ((polymeth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solewnt near extraction  ((polymeth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueo		102	and extraction) and metal near removes?	1	
0			and photoresist	1	14:23
-			Processor Processor		
and aqueous near oxalic and aqueous near oxalic (polymerization and poly(meth)acrylate and extraction) and aqueous near oxalic  (polymerization and poly(meth)acrylate and extraction) and aqueous near oxalic  (polymerization and poly(meth)acrylate and extraction) and aqueous near acid  ((polymerization and poly(meth)acrylate and extraction) and aqueous near acid  ((polymerization and poly(meth)acrylate and extraction) and aqueous near acid  ((polymerization and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and photoresist  ((polymerization and poly(meth)acrylate and extraction) and photoresist and extraction) and photoresist  ((polymerization and poly(meth)acrylate and extraction) and photoresist and extraction) and photoresist and extraction) and photoresist  ((polymerization and poly(meth)acrylate and extraction) and photoresist and extraction) and photoresist  ((polymeth)acrylate with reduc\$4 near metal near content  (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist  (polyment)  (polyment)  (polyment)  (polyment	-	0	((polymerization and poly(meth)acrylate	l .	2002/12/03
Comparization and poly(meth)acrylate and extraction and aqueous near oxalic   Comparization and poly(meth)acrylate and extraction and aqueous near acid and extraction and aqueous near acid and extraction and aqueous near acid and extraction and aqueous near acid and extraction and aqueous near acid and extraction and poly(meth)acrylate and extraction and poly(meth)acrylate and extraction and poly(meth)acrylate and extraction and poly(meth)acrylate and extraction and poly(meth)acrylate and extraction and photoresist   US-PGPUB; EPO; JPO; DERWENT   US-PGPUB; EPO; JPO; D			and extraction) and metal near remov\$3)	1	
Colymerization and poly(meth)acrylate and extraction) and aqueous near oxalic   Colymerization and poly(meth)acrylate and extraction) and aqueous near acid   Colymerization and poly(meth)acrylate and extraction) and aqueous near acid   Colymerization and poly(meth)acrylate and extraction) and aqueous near acid   Colymerization and poly(meth)acrylate and extraction) and aqueous near acid   Colymerization and poly(meth)acrylate and extraction) and photoresist   Colymerization and poly(meth)acrylate and extraction) and photoresist   Colymerization and poly(meth)acrylate and extraction)   Colymerization and poly(meth)acrylate and extraction)   Colymerization and poly(meth)acrylate and extraction)   Colymerization and photoresist   Colymerization   Col			and aqueous near oxalic		
and extraction) and aqueous near oxalic  (polymerization and poly(meth)acrylate and extraction) and aqueous near acid  (polymerization and poly(meth)acrylate and extraction) and aqueous near acid  (polymerization and poly(meth)acrylate and extraction) and aqueous near acid) and ((polymerization and poly(meth)acrylate and extraction) and metal near remov\$3)  (polymerization and poly(meth)acrylate and extraction) and photoresist  (polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  ((polymeth)acrylate with reduc\$4 near metal near content  496582 poly(meth)acrylate with reduc\$4 with metal with content  poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)a	_	101	(nolement action and 3 ( ))		
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- 4575 (polymerization and poly(meth)acrylate and extraction) and aqueous near acid  78 ((polymerization and poly(meth)acrylate and extraction) and aqueous near acid)  8			and everagerent, and addeeds bear exalle	1	1 15:04
- 49575 (polymerization and poly(meth)acrylate and extraction) and aqueous near acid (polymerization and poly(meth)acrylate and extraction) and aqueous near acid) and ((polymerization and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and poly(meth)acrylate and extraction) and photoresist (polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid (polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid (polymeth)acrylate with reduc\$4 near metal near content (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with whereal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with whereal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with with with with with with with with					
and extraction) and aqueous near acid  ((polymerization and poly(meth) acrylate and extraction) and aqueous near acid) and ((polymerization and poly(meth) acrylate and extraction) and metal near remov\$3)  (polymerization and poly(meth) acrylate and extraction) and photoresist  and extraction) and photoresist  ((polymerization and poly(meth) acrylate and extraction) and photoresist  and extraction) and photoresist  ((polymerization and poly(meth) acrylate and extraction) and photoresist) and aqueous near acid  Poly(meth) acrylate with reduc\$4 near metal near content  (poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth) acrylate with reduc\$4 with meta	-	4575	(polymerization and poly(meth)acrylate		2002/12/03
- 188 (((polymerization and poly(meth)acrylate and extraction) and aqueous near acid) and ((polymerization and poly(meth)acrylate and extraction) and metal near remov\$3)  - 3585 ((polymerization and poly(meth)acrylate and extraction) and photoresist  - 136 (((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  - 136 (((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  - 136 (((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  - 136 (((polymerization and poly(meth)acrylate with reduc\$4 near metal near content  - 136 (((polymerization and poly(meth)acrylate with reduc\$4 with metal with content)  - 136 ((((polymerization and poly(meth)acrylate with reduc\$4 with metal with content)  - 136 (((((polymerization and polymeth)acrylate with reduc\$4 with metal with content)  - 136 (((((((((((((((((((((((((((((((((((			and extraction) and aqueous near acid	1	
Total			_	EPO; JPO;	
and extraction) and aqueous near acid) and ((polymerization and poly(meth)acrylate and extraction) and metal near remov\$3)  (polymerization and poly(meth)acrylate and extraction) and photoresist  - 136 ((polymerization and poly(meth)acrylate and extraction) and photoresist)  - 136 ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  - 2496582 poly(meth)acrylate with reduc\$4 near metal near content  - 2496590 poly(meth)acrylate with reduc\$4 with metal with content  - 2496590 poly(meth)acrylate with reduc\$4 with metal with content  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solvent near extraction  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  - 3496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and pho		7.0		li .	
and ((polymerization and poly(meth)acrylate and extraction) and metal near remov\$3)  (polymerization and poly(meth)acrylate and extraction) and photoresist  - 136 ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid - 496582 poly(meth)acrylate with reduc\$4 near metal near content  - 1844 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 w	-	/8	((polymerization and poly(meth)acrylate		
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metal near remov\$3) (polymerization and poly(meth)acrylate and extraction) and photoresist  136 ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  136 ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  137 136 ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  137 137 138 138 ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous with acid and photoresist and solevnt near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with			poly(meth)acrylate and extraction) and		
and extraction) and photoresist    US-PGPUB; EFO; JPO; DERWENT USPAT; US-PGPUB; and extraction) and photoresist) and aqueous near acid   US-PGPUB; and extraction) and photoresist) and aqueous near acid   US-PGPUB; EFO; JPO; DERWENT USPAT; US-PGPUB; EFO; JPO; DE			metal near remov\$3)	DEIWENT.	
- 136 ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  - 496582 poly(meth)acrylate with reduc\$4 near metal near content  - 496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 0 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near ex	-	3585		USPAT;	2002/12/03
Comparization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid   Comparization and photoresist) and aqueous near acid   Comparization and photoresist)   Comparization and extraction   Comparization and photoresist   Comparization and extraction   Comparization and photoresist   Comparization   Compariz			and extraction) and photoresist		16:09
- 136 ((polymerization and poly(meth)acrylate and extraction) and photoresist) and aqueous near acid  - 496582 poly(meth)acrylate with reduc\$4 near metal near content  - 496590 poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 0 ((poly(meth)acrylate with red					
and extraction) and photoresist) and aqueous near acid  496582 poly(meth) acrylate with reduc\$4 near uspAT;	_	136	((nolymerization and noly(meth)acrylate		2002/12/02
aqueous near acid  496582 poly(meth) acrylate with reduc\$4 near uspar; metal near content  496590 poly(meth) acrylate with reduc\$4 with metal with content  1844 (poly(meth) acrylate with reduc\$4 with aqueous with acid  0 ((poly(meth) acrylate with reduc\$4 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth) acrylate with reduc\$4 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth) acrylate with reduc\$4 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth) acrylate with reduc\$4 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction ((poly(meth) acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction ((poly(meth) acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction ((poly(meth) acrylate with reduc\$4 with uspar; usp		130			
- 496582 poly(meth)acrylate with reduc\$4 near uspat; uspat					10.17
- 496582 poly(meth)acrylate with reduc\$4 near metal near content  496590 poly(meth)acrylate with reduc\$4 with metal with content  (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid and photoresist and solevnt near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist  50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist  50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist  50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist  50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist  50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and sole with acid) and photoresist and approximate with acid) and photoresist and approximate with acid) and photoresist and approximate with acid) and photoresist and approximate with acid) and photoresist and approximate with acid) and photoresist and approximate with acid					
- 496590 poly(meth)acrylate with reduc\$4 with metal with content  - 1844 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 50 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 50 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent permital with content) and contact\$3 with aqueous with acid) and photoresist and solvent permital with content) and contact\$3 with aqueous with acid) and photoresist and solvent permital with content) and contact\$3 with aqueous with acid) and photoresist and solvent permital with content) and contact\$3 with add with permital with pe	-	496582			2002/12/03
- 496590 poly(meth)acrylate with reduc\$4 with metal with content  1844 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  10 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  10 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  10 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  10 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  10 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  10 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction berwent uspat; 2002/12/03 and 2002/12/03			metal near content		1
- 496590 poly(meth)acrylate with reduc\$4 with metal with content  - 1844 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction - 0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 50 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction - 50 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist with uspat; - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist with uspat; - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist with uspat; - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist with uspat; - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist with uspat; - 50 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth)acrylate with reduc\$4 with uspat; - 50 (poly(meth					
metal with content  1844 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  1844 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  1844 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solevnt near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction  1844 (poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and aqueous with acid) and photoresist and aqueous with acid) and photoresist and aqueous with acid) and photoresist and aqueous with acid) and photoresist and aqueous with acid) and photoresist and aqueous acid acid acid acid acid acid acid acid	_	496590	noly(meth)acrylate with roduce4 with	l :	2002/12/02
The second secon		420390		· · · •	
- 1844 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  0 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction  10 ((poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solevnt near extraction  10 ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  10 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  10 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with metal with content) and contact\$3 with uspat;  10 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with metal with content) and contact\$3 with uspat;  10 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with uspat;  10 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with uspat;  10 (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with uspat;  11 (poly(meth)acrylate with reduc\$4 with uspat;  12 (poly(meth)acrylate with reduc\$4 with uspat;  13 (poly(meth)acrylate with reduc\$4 with uspat;  14 (poly(meth)acrylate with reduc\$4 with uspat;  15 (poly(meth)acrylate with reduc\$4 with uspat;  16 (poly(meth)acrylate with reduc\$4 with uspat;  16 (poly(meth)acrylate with reduc\$4 with uspat;  17 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (poly(meth)acrylate with reduc\$4 with uspat;  18 (	]				10.22
- 1844 (poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid  - 0 (poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction (poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction (poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction (poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction (poly(meth) acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist EPO; JPO; metal with content) and contact\$3 with aqueous with acid) and photoresist EPO; JPO;					
aqueous with acid  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with metal with content) and contact\$3 with uspat; uspat; metal with content) and contact\$3 with uspat; uspat; aqueous with acid) and photoresist epo; Jpo; because the poly Jpo; aqueous with acid) and photoresist epo; Jpo; less the property of the	-	1844		USPAT;	2002/12/03
O ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction ((poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist EPO; JPO; metal with acid) and photoresist EPO; JPO;					16:23
O ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction ((poly(meth)acrylate with reduc\$4 with aqueous with acid) and photoresist and solvent near extraction ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction (poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist EPO; JPO;			aqueous with acid		
metal with content) and contact\$3 with aqueous with acid) and photoresist and solevnt near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist  EPO; JPO;  DERWENT USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; USPAT; EPO; JPO; EPO; JPO; EPO; JPO; EPO; JPO;	_	0	((poly(meth)acrylate with roduct4 with		2002/12/02
aqueous with acid) and photoresist and solevnt near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with uspat; uspat; uspat; metal with content) and contact\$3 with uspat; u		١			
solevnt near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with uspat; uspat; uspat; metal with content) and contact\$3 with uspat; uspat					
metal with content) and contact\$3 with aqueous with acid) and photoresist and solvent near extraction ((poly(meth)acrylate with reduc\$4 with (US-PGPUB; DERWENT (USPAT; Metal with content) and contact\$3 with us-PGPUB; aqueous with acid) and photoresist EPO; JPO;			solevnt near extraction		
aqueous with acid) and photoresist and solvent near extraction  ((poly(meth)acrylate with reduc\$4 with metal with content) and contact\$3 with aqueous with acid) and photoresist  EPO; JPO; DERWENT USPAT; USPAT; US-PGPUB; 16:29  EPO; JPO;	-	0	((poly(meth)acrylate with reduc\$4 with		
solvent near extraction  ((poly(meth)acrylate with reduc\$4 with uspat; uspat; uspat; uspat; aqueous with acid) and photoresist EPO; JPO;			metal with content) and contact\$3 with		16:24
- 50 ((poly(meth)acrylate with reduc\$4 with USPAT; 2002/12/03 metal with content) and contact\$3 with US-PGPUB; aqueous with acid) and photoresist EPO; JPO;					
metal with content) and contact\$3 with US-PGPUB; 16:29 aqueous with acid) and photoresist EPO; JPO;	-	50			2002/12/03
aqueous with acid) and photoresist EPO; JPO;		55	metal with content) and contact\$3 with	I	
			aqueous with acid) and photoresist		10.25

-	18	( (f ) ( ) menjames bane pricestation	USPAT;	2002/12/03
		same purif\$8) same metal same content)	US-PGPUB;	16:38
		and washing near3 acid	EPO; JPO;	ł
			DERWENT	ļ
-	814287		USPAT;	2002/12/03
		poly(meth)acrylate	US-PGPUB;	16:40
			EPO; JPO;	
			DERWENT	
-	870738		USPAT;	2002/12/03
		poly(meth)acrylate	US-PGPUB;	17:02
			EPO; JPO;	
			DERWENT	
-	792291	process same reduc\$3 metal same content	USPAT;	2002/12/03
		same poly(meth)acrylate	US-PGPUB;	16:57
			EPO; JPO;	
			DERWENT	
_	32		USPAT;	2002/12/03
		content same poly(meth)acrylate) and	US-PGPUB;	16:42
		wash near aqueous near acid	EPO; JPO;	
			DERWENT	
-	797019	1	USPAT;	2002/12/03
		and poly(meth)acrylate	US-PGPUB;	16:57
			EPO; JPO;	
			DERWENT	
-	660739	process same reduc\$3 metal same content	USPAT;	2002/12/03
1			US-PGPUB;	16:59
			EPO; JPO;	10.55
			DERWENT	
_	2	contact\$3 near solvent near aqueous	USPAT;	2002/12/03
	_	near acid	US-PGPUB;	16:59
		ar acra	1	16:59
			EPO; JPO;	
_	3600	/process same reduct? metal same	DERWENT	10000400400
	3000	(process same reduc\$3 metal same content) and polymethacrylate	USPAT;	2002/12/03
		concent) and polymethacrylate	US-PGPUB;	17:01
			EPO; JPO;	
_	0	//	DERWENT	
_		( \P-0000 banc readeqs meear same	USPAT;	2002/12/03
		content) and polymethacrylate) and	US-PGPUB;	17:00
		(extract\$4 near solvent near aqueous	EPO; JPO;	
_	15	near acid)	DERWENT	
_	15	extract\$4 near solvent near aqueous	USPAT;	2002/12/03
		near acid	US-PGPUB;	17:00
			EPO; JPO;	
	3.55	//	DERWENT	
_	166		USPAT;	2002/12/03
		content) and polymethacrylate) and	US-PGPUB;	17:01
:		photoresist	EPO; JPO;	
			DERWENT	
-	2590	(method same reduc\$3 metal same	USPAT;	2002/12/03
		poly(meth)acrylate) and ((process same	US-PGPUB;	17:02
		reduc\$3 metal same content) and	EPO; JPO;	
		polymethacrylate)	DERWENT	
-	138	((method same reduc\$3 metal same	USPAT;	2002/12/03
		poly(meth)acrylate) and ((process same	US-PGPUB;	17:05
		reduc\$3 metal same content) and	EPO; JPO;	
		polymethacrylate)) and photoresist	DERWENT	
-	1	polyacrylate with reduced with metal	USPAT;	2002/12/03
		with content	US-PGPUB;	17:06
			EPO; JPO;	
			DERWENT	
-	496728	poly(meth)acrylate with reduced with	USPAT;	2002/12/03
		metal with content	US-PGPUB;	17:06
			EPO; JPO;	
			DERWENT	
-	0	polymethacrylate with reduced with	USPAT;	2002/12/03
		metal with content	US-PGPUB;	17:06
			EPO; JPO;	
			DERWENT	

-	5	acrylate with reduced with metal with content	USPAT; US-PGPUB;	2002/12/03 17:08
			EPO; JPO; DERWENT	
_	225	polymer with reduc\$3 with metal with	USPAT;	2002/12/03
		content	US-PGPUB; EPO; JPO;	17:09
	142		DERWENT	
_	142	polymer with reduced with metal with content	USPAT; US-PGPUB;	2002/12/03
			EPO; JPO;	17.10
_	3011096	remov\$3 metal near polyacrylate	DERWENT USPAT;	2002/12/03
		polytonia moral moral polytonia	US-PGPUB;	17:28
			EPO; JPO; DERWENT	
_	0	removal near metal near polyacrylate	USPAT;	2002/12/03
			US-PGPUB;	17:12
			EPO; JPO; DERWENT	
-	35	The second secon	USPAT;	2002/12/03
		polyacrylate	US-PGPUB; EPO; JPO;	17:13
			DERWENT	
_	691	(remov\$3 metal near polyacrylate) and solvent near aqueous near acid	USPAT; US-PGPUB;	2002/12/03 17:25
	] [	sorvene near aqueous hear acru	EPO; JPO;	17:25
_	229	((remov\$3 metal near polyacrylate) and	DERWENT	2000 (12 (22
	223	solvent near aqueous near acid) and	USPAT; US-PGPUB;	2002/12/03 17:25
		extraction	EPO; JPO;	
_	68007	(remov\$3 metal near polyacrylate) and	DERWENT USPAT;	2002/12/03
		ion near exchange	US-PGPUB;	17:29
			EPO; JPO; DERWENT	
-	2	("5466745").PN.	USPAT;	2002/12/03
			US-PGPUB; EPO; JPO;	17:44
			DERWENT	
-	1	("60005045").PN.	USPAT; US-PGPUB;	2002/12/03
			EPO; JPO;	17:37
_	2	("6005045").PN.	DERWENT	2002/10/22
		( 0000040 /	USPAT; US-PGPUB;	2002/12/03 17:37
			EPO; JPO;	
-	2	("6046276").PN.	DERWENT USPAT;	2002/12/03
			US-PGPUB;	17:42
			EPO; JPO; DERWENT	
-	2	("5916992").PN.	USPAT;	2002/12/03
			US-PGPUB; EPO; JPO;	17:43
		//NEACCTAEH	DERWENT	
_	2	(("5466745").PN.)	USPAT; US-PGPUB;	2002/12/03 17:44
			EPO; JPO;	
_	9	"5466745"	DERWENT USPAT;	2002/12/03
			US-PGPUB;	17:44
			EPO; JPO;	
			DERWENT	